

# The SPI Supplies Family of Instruments



Excellence in sample preparation  
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Your results will never be better than your sample preparation. See how SPI Supplies can help you deliver the highest quality results for all your SEM/EDS, TEM and FESEM applications.

1. **Osmium Plasma Coaters**  
for FESEM Applications
2. **SPI-MODULE™**  
Sputter/Carbon Coater Module
3. **Gentle Mill™**  
Ion Milling System
4. **Plasma Prep™ III Solid State**  
Plasma Cleaner for cleaning TEM holders

5. **Plasma Prep™ X**  
Parallel Plate Plasma Etcher
6. **Plasma Prep™ III Plasma Etcher**  
with **PPIII Process Controller**
7. **Vacu Prep™ II**  
Turbo Pump Evaporation System
8. **SPI-DRY™**  
Critical Point Dryer
9. **Precision Spin Coater**  
Spin coater



**SPI Supplies Division of STRUCTURE PROBE, Inc.**

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### SPI Module™ Sputter/Carbon Coaters

Combination sputter/carbon coater system for everyday routine SEM/EDS sample preparation. Fast and easy to use.



### Gentle Mill Ion Beam Workstation

Ion Mill system for the highest quality and damage free XTEM, HRTEM or STEM samples.

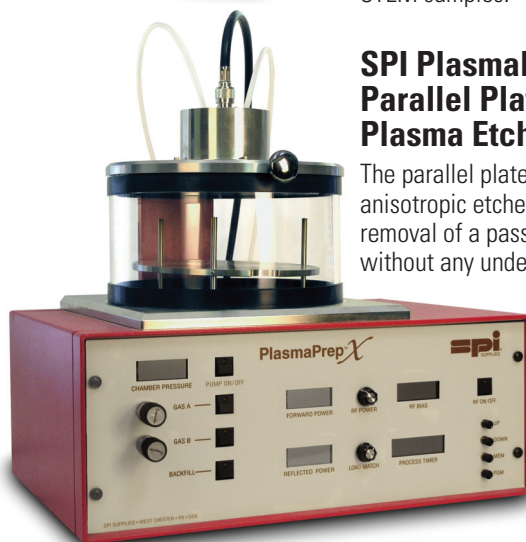


### Plasma Prep™ III

Solid state compact tabletop design with RF power range of 1 to 100W. The Plasma Prep™ III Process Controller: Add-on module with multiple gas inputs and process timer control.

### SPI Plasma Prep™ III Plasma Cleaner

Compact bench-top sized plasma cleaner, that uses the "dry plasma process" for the removal of contamination on the TEM specimen stages



### SPI PlasmaPrep™ X Parallel Plate Plasma Etcher

The parallel plate design of an anisotropic etcher permits the removal of a passivation layer without any undercutting.

### SPI Supplies Vacu Prep™ II

Fast, clean, efficient, turbo-pumped, high vacuum bench-top evaporator with simple automated operation for evaporation or sputtering.



### Osmium Plasma Coaters

The must have coater for high resolution FE-SEM work. Typical thickness of 1nm to 3nm of osmium metal, with excellent electrical and thermal conductivity and a virtually "amorphous" coating with no discernible grain structure.



### SPI-Dry™ Critical Point Dryers

Used in applications in electron microscopy as well as aerogels and MEMS, the critical point drying is a method of drying samples without collapsing or deforming the structure of wet, fragile specimens.



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